

Form PTO 1449 (Rev. 2-32)	U.S. Department of Commerce Patent and Trademark Office	Atty. Docket No. LMPY-10910	Serial No.: 09/733,874
Information Disclosure Statement by Applicant		Applicant: Michael J. Scaggs	
(Use several sheets if necessary)		Filed: December 8, 2000 Group: 2881	

U.S. Patent Documents

Init.	Document No.	Date	Name	Class	Subclass	Filing Date
2	4,258,334	03/24/81	McCuster, et al.	331	94.5 G	05/17/76
3	4,393,505	07/12/83	Fahlen	372	57	11/03/81
3	4,616,908	10/14/86	King	350	576	07/19/84
2	5,051,558	09/24/91	Sukhman	219	121.68	03/20/89
2	5,057,184	10/15/91	Gupta, et al.	156	637	04/06/90
2	5,221,823	06/22/93	Usui	219	121.78	01/17/92
2	5,440,587	08/08/95	Ishikawa et al.	375	332	07/08/94
2	5,450,436	09/12/95	Mizoguchi et al.	372	59	11/19/93
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2	5,590,146	12/31/96	von Borstel	372	58	05/19/95
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2	5,761,236	06/02/98	Kleinschmidt et al.	372	100	07/18/96
2	5,763,855	06/09/98	Shioji	219	121.84	06/02/95
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2	5,841,099	11/24/98	Owen, et al.	219	121.69	05/17/96

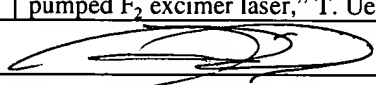
Foreign Documents

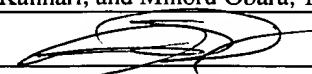
Translation							
Init.	Document No.	Date	Country	Class	Subclass	Yes	No
2	JP 408055792A	02/27/96	Japan	H01L	21/027	X (Abstract)	
2	EP 0 790 681 A2	08/20/97	EPO	H01S	3/134	X	
2	WO 98/57213	12/17/98	PCT	G02B	27/00		X
2	WO 98/59364	12/30/98	PCT	H01L	21/027		X
2	WO 99/04467	01/28/99	PCT	H01S	3/134	X	
2	WO 99/08133	02/18/99	PCT	G03B	27/42	X	
2	EP 1 017 086 A1	07/05/00	EPO	H01L	21/057	X	

Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)

2	T. Y. Chang, "Improved Uniform-Field Electrode Profiles for TEA Laser and High-Voltage Applications," <u>The Review of Scientific Instruments</u> , Vol 44, No. 4, April 1973, pp. 405-407.
3	<i>Applied Physics Letters</i> , Vol. 31, No. 1, July 1, 1977, "vuv emissions from mixtures of F ₂ and the noble gasses--A molecular F ₂ laser at 1575 Å ⁰ ," James K. Rice, A. Kay Hays, and Joseph R. Woodsworth, 5 pgs.
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Examiner: Initial if citation considered, whether or not citation is in conference with MPEP 609; Draw line through citation if not conformance and not considered. Include a copy of this form with the next communication to applicant.	

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7	Optics Communications, Vol. 28, No. 1, January 1979, "Discharge pumped F ₂ Laser at 1580 Å", H. Pummer, K. Hohla, M. Diegelmann and J.P. Reilly," pp. 104-106.		
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<div style="position: absolute; left: 30px; top: 140px; border: 1px solid black; border-radius: 50%; padding: 5px; text-align: center;"> O I P E DEC 18 2001 PATENT & TRADEMARK OFFICE </div> Information Disclosure Statement by Applicant		Applicant: Michael J. Scaggs	
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Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)			
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1	Applied Physics Letters, Vol. 54, February 13, 1989, No. 7, "High-power discharge-pumped F ₂ molecular laser," Kawakatsu Yamada, Kenzo Miyazaki, Toshifumi Hasama, and Takuzo Sata, 6 pgs.		
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